

AMENDMENTS TO THE CLAIMS

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

Please cancel claims 25-33 without prejudice or disclaimer of its subject matter, as follows:

1 1. (Original) A tension mask for a color cathode-ray tube, comprising:
2 a plurality of parallel strips separated by a predetermined distance from each other;
3 a plurality of real bridges intersecting adjacent strips among said plurality of parallel strips
4 to define slots, the slots accommodating electron beams to pass through; and
5 a plurality of dummy bridges located in the slots, partially extending between but not
6 intersecting the adjacent strips, said plurality of dummy bridges having projections facing each other
7 without touching, said dummy bridges having an etching boundary located below the middle of said
8 strips.

1 2. (Original) The tension mask of claim 1, with said plurality of real bridges being recessed
2 by a predetermined depth from the top surface of said real bridges, and the thickness of each of said
3 real bridges being smaller at the center than at the periphery of said real bridges.

1 3. (Original) The tension mask of claim 2, with the thickness of each of one said real bridges

2 at the recessed center of the real bridges being approximately the same as the distance from the
3 bottom of the strips to said etching boundaries of said dummy bridges.

1 4. (Original) The tension mask of claim 1, with each of said plurality of real bridges having
2 a planar top surface.

1 5. (Original) The tension mask of claim 4, with the top or bottom surface of said real bridges
2 being at the same level as the surfaces of said adjacent strips.

1 6. (Original) The tension mask of claim 1, with the distance from the bottom of said strips
2 to the etching boundaries of said dummy bridges being 0.25 times smaller than the thickness of said
3 strips.

1 7. (Original) The tension mask of claim 6, with the thickness of each of said real bridges at
2 the recessed center of said real bridges being approximately the same as the distance from the bottom
3 of said strips to the etching boundaries of said dummy bridges.

1 8. (Original) The tension mask of claim 1, with the distance from the top of the strips to the
2 etching boundaries of said dummy bridges being larger than the distance from the bottom of the
3 strips to the etching boundaries of said dummy bridges, the top of the strips being on the electron
4 beam emitting side and the bottom of the strips being on the electron beam entering side.

1 9. (Original) The tension mask of claim 1, with the relative position of each of the slots at
2 the beam entering side with respect to the beam emitting side of said tension mask being shifted
3 toward the center of said tension mask as the locations of the slots become closer to the periphery
4 of said tension mask.

1 10. (Original) The tension mask of claim 9, with the relative position of each of the slots at
2 the beam entering side being shifted toward the center of said tension mask by etching a portion of
3 each slot on the beam emitting side with a predetermined width, and shifting an etch of a portion of
4 each slot on the beam emitting side with a predetermined width towards the center of said tension
5 mask with respect to the etch of the portion of the slot on the beam emitting side, the etch on the
6 beam emitting side and the etch on the beam entering side forming one of the slots of said tension
7 mask.

1 11. (Original) The tension mask of claim 9, with the center of said tension mask being a
2 center line accross a width of said tension mask.

1 12. (Original) The tension mask of claim 1, with the relative position of the gap between the
2 facing dummy bridges being shifted toward the center or the periphery of said tension mask as the
3 locations of said dummy bridges become closer to the periphery of said tension mask.

1 13. (Original) The tension mask of claim 12, with the relative position of the gap between
2 the facing dummy bridges being shifted toward the center or the periphery of said tension mask
3 according to the reduction of the clipping of the electron beams.

1 14. (Original) The tension mask of claim 1, with the width of each of said dummy bridges
2 along said strips becoming narrow as the locations of said dummy bridges come closer to the
3 periphery of said tension mask.

1 15. (Original) The tension mask of claim 12, with the width of each of said dummy bridges
2 along said strips becoming narrow as the locations of said dummy bridges come closer to the
3 periphery of said tension mask.

1 16. (Original) The tension mask of claim 1, with the area of each of the dummy bridges
2 becoming smaller as the locations of the dummy bridges come closer to the periphery of the tension
3 mask.

1 17. (Original) The tension mask of claim 1, with said adjacent strips having rounded portions
2 to reduce the clipping of electron beams.

1 18. (Previously Presented) The tension mask of claim 1, with the width of each of the slots
2 at the electron beam emitting side being wider than at the electron beam entering side.

1 19. (Original) The tension mask of claim 1, being manufactured by an exposure mask
2 comprising a pair of upper and lower exposure masks to be aligned over the top and bottom surfaces
3 of a steel foil, respectively, to accommodate exposure of photosensitive layers deposited on said steel
4 foil, said upper exposure mask having a pattern including a series of parallel upper light transmission
5 portions arranged in lines, said lower exposure mask comprising:

6 a pattern including a series of parallel lower light transmission portions arranged in lines;

7 a plurality of first light shielding portions intersecting adjacent lower light transmission
8 portions among said series of parallel lower light transmission portions; and

9 a plurality of second light shielding portions partially extending between the adjacent lower
10 light transmission portions.

1 20. (Original) A tension mask for a color cathode-ray tube, comprising:

2 a plurality of parallel strips separated by a predetermined distance from each other;

3 a plurality of real bridges intersecting adjacent strips among said plurality of parallel strips
4 to define slots accommodating electron beams to pass through;

5 a plurality of dummy bridges located in the slots, partially extending between but not
6 intersecting the adjacent strips, said dummy bridges facing each other, an etching boundary of each
7 of said dummy bridges being located below the middle of said strips;

8 a pair of first rounded portions formed with a first thickness at the beam emitting side of each
9 of the slots, partially extending from the adjacent strips; and

10 a pair of second rounded portions formed with a second width at the beam entering side of
11 each of the slots, partially extending from the adjacent strips.

1 21. (Original) The tension mask of claim 20, with the relative position of each of the slots
2 at the beam entering side with respect to the beam emitting side being shifted toward the center of
3 the tension mask as the locations of the slots come closer to the periphery of the tension mask.

1 22. (Original) The tension mask of claim 20, with the relative position of the gap between
2 the facing dummy bridges being shifted toward the center or the periphery of said tension mask as
3 the locations of said dummy bridges come closer to the periphery of said tension mask.

1 23. (Original) The tension mask of claim 20, with said plurality of real bridges being
2 recessed by a predetermined depth from the top surface of said real bridges, and the thickness of each
3 of said real bridges being smaller at the center than at the periphery of said real bridges.

1 24. (Original) The tension mask of claim 20, with each of said plurality of real bridges
2 having a planar top surface.

Claims 25-33 (Cancelled)